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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/661,832	09/12/2003	Qing Hu	101328-0177	. 7715
21125	7590 07/21/2005		EXAMINER VAN ROY, TOD THOMAS	
	CCLENNEN & FISH	LLP		
WORLD TRADE CENTER WEST 155 SEAPORT BOULEVARD BOSTON, MA 02210-2604			ART UNIT	PAPER NUMBER
			2828	

DATE MAILED: 07/21/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

		AX	
	Application No.	Applicant(s)	
	10/661,832	HU ET AL.	
Office Action Summary	Examiner of which	Art Unit	_
	Tod T. Van Roy	2828	
The MAILING DATE of this communication Period for Reply	appears on the cover sheet with	the correspondence address	
A SHORTENED STATUTORY PERIOD FOR RE THE MAILING DATE OF THIS COMMUNICATIO  - Extensions of time may be available under the provisions of 37 CFF after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a  - If NO period for reply is specified above, the maximum statutory per  - Failure to reply within the set or extended period for reply will, by state of the period for reply will, by state of the period for reply will, by state of the period for reply will.  - Failure to reply within the set or extended period for reply will, by state of the period for reply will.  - Failure to reply within the set or extended period for reply will, by state of the period for reply will.	N. R 1.136(a). In no event, however, may a repreply within the statutory minimum of thirty fod will apply and will expire SIX (6) MONT atute, cause the application to become ABA	ly be timely filed  (30) days will be considered timely.  4S from the mailing date of this communication.  NDONED (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on			
,	This action is non-final.		
3) Since this application is in condition for allo	wance except for formal matter	rs, prosecution as to the merits is	
closed in accordance with the practice unde			
Disposition of Claims			
4)⊠ Claim(s) 1-18 is/are pending in the applicat	ion.		
4a) Of the above claim(s) is/are without	drawn from consideration.		
5) Claim(s) is/are allowed.		·	
6) Claim(s) 1-18 is/are rejected.	•	·	
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction an	d/or election requirement.		
Application Papers			
9)☐ The specification is objected to by the Exam	iner.		
10) The drawing(s) filed on is/are: a) a	accepted or b) Objected to by	the Examiner.	
Applicant may not request that any objection to	the drawing(s) be held in abeyanc	e. See 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the cor	rection is required if the drawing(s	) is objected to. See 37 CFR 1.121(d).	
11)☐ The oath or declaration is objected to by the	Examiner. Note the attached	Office Action or form PTO-152.	
Priority under 35 U.S.C. § 119			
<ul> <li>12) Acknowledgment is made of a claim for fore</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority docum</li> <li>2. Certified copies of the priority docum</li> </ul>	ents have been received.		
<ol><li>Copies of the certified copies of the p</li></ol>	riority documents have been re	eceived in this National Stage	
application from the International Bur	eau (PCT Rule 17.2(a)).		
* See the attached detailed Office action for a	list of the certified copies not re	eceived.	
Attachment(s)			
1) Notice of References Cited (PTO-892)	4) Interview Su		
<ol> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/SB.</li> </ol>		Mail Date omal Patent Application (PTO-152)	
Paper No(s)/Mail Date <u>02/27/2004</u> .	6) Other:	, , , , , , , , , , , , , , , , , , , ,	

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#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claims 16-17 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention.

With respect to claim 16, the specification discloses the formation of the active region via MBE, and the metal layers being "deposited" thereafter without disclosing the deposition methods. It is believed that the deposition of the metal is by e-beam techniques, (equipment enabling this is understood to be incorporated into some MBE systems), and has been examined as such.

With respect to claim 17, the specification discloses the deposition of metal layers, followed by a wafer bonding technique. This does not correspond to the claim language stating the metal layers are "generated" using wafer bonding. This claim has been examined as meaning the formation of the overall structure involves a wafer bonding technique.

#### Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 15 and 17 are rejected under 35 U.S.C. 102(b) as being anticipated by Unterrainer et al. (Unterrainer et al., Quantum cascade lasers with double metal-semiconductor waveguide resonators," Appl Phys. Lett. 80. 3060 (2002)).

With respect to claim 15, Unterrainer discloses a method of confining a mode profile of radiation in a quantum cascade laser comprising: disposing an active region of said quantum cascade laser between an upper and a lower metallic layer (col.3 lines 25-27), wherein each metallic layer has a thickness larger than a skin depth of radiation in a frequency range of about 1 THz to about 10 THz (col.2 lines 36-37 bottom layer-2um, col.3 lines 18-19 top layer 300nm).

With respect to claim 17, Unterrainer discloses the use of a wafer bonding technique to form the structure (col.2 lines 34-39).

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:

- 1. Determining the scope and contents of the prior art.
- 2. Ascertaining the differences between the prior art and the claims at issue.
- 3. Resolving the level of ordinary skill in the pertinent art.
- 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

Claims 1-6, and 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Unterrainer et al. (Unterrainer et al., Quantum cascade lasers with double metal-semiconductor waveguide resonators," Appl Phys. Lett. 80. 3060 (2002)) in view of Xu et al. (Xu and Hu, "Electrically pumped tunable terahertz emitter based on intersubband transition," American Institute of Physics (1997)).

With respect to claim 1, Uterrainer teaches an active region for generating THz radiation (col.2 lines 13-15), and a waveguide formed of an upper and lower metallic layer disposed on a surface of said active layer (col.3 lines 25-27) so as to confine selected modes of said lasing radiation within said active region. Uterrainer does not teach the active region to emit at about 1 to about 10 THz. Xu teaches an active region for generating THz radiation that emits from about 1 to about 10 THz (fig.3). It would have been obvious to one of ordinary skill in the art at the time of the invention to combine the THz radiation emitter and waveguide of Unterrainer with the active region of Xu in order to take advantage of the fast depopulation possible through LO-phonon scattering occurring in this material at this frequency range (col.2-3 lines 10-4, fig.3).

With respect to claim 2, Unterrainer and Xu teach the cascade laser outlined in the rejection to claim 1, and further teach the waveguide to have a mode confinement factor of about 1 (Unterrainer, col.2 line 8).

With respect to claim 3, Unterrainer and Xu teach the cascade laser outlined in the rejection to claim 1, and further teach the metallic layers to have a thickness in the range of about .1 to several microns (Unterrainer, col.2 lines 36-37 bottom layer-2um, col.3 lines 18-19 top layer 300nm).

With respect to claims 4 and 6, Unterrainer and Xu teach the cascade laser outlined in the rejection to claim 1, and further teach at least one of the metallic layers to comprise a single layer formed of a selected metallic compound (Unterrainer, col.2 lines 35-37).

With respect to claim 5, Unterrainer and Xu teach the cascade laser outlined in the rejection to claim 1, and further teach one of said metallic layers to comprise a multi-layer structure, being formed by at least two different metallic compounds (Unterrainer, col.3 lines 10-19, top layer comprised of a Ti/Au pad surrounded by additional Au).

With respect to claim 8, Unterrainer and Xu teach the cascade laser outlined in the rejection to claim 1, and further teach the active region to comprise a semiconductor heterostructure providing a plurality of lasing modules connected in series (Unterrainer, col.2 lines 21-32).

Claims 1, 4, 6, 9-13, and 18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Xu in view of Unterrainer.

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With respect to claims 1 and 10, Xu teaches an active region for generating lasing radiation in a frequency range of about 1 to 10 THz (fig.3) including the active region being surrounded by two contact layers (col.1 lines 25-30). Xu does not teach a waveguide formed of metal to confine selected modes of lasing radiation within the active region. Unterrainer teaches an active region, sandwiched by two contact layers (col.2 lines 26-27), for generating THz radiation (col.2 lines 13-15), and a waveguide formed of an upper and lower metallic layer disposed on a surface of said active region (col.3 lines 25-27) so as to confine selected modes of said lasing radiation within said active region. It would have been obvious to one of ordinary skill in the art at the time of the invention to combine the cascade laser of Xu with the metallic waveguide of Unterrainer to obtain high optical confinement factors with low waveguide loss (Unterrainer, abs.).

With respect to claims 4 and 6, Xu and Unterrainer teach the cascade laser outlined in the rejection to claim 1, and further teach at least one of the metallic layers to comprise a single layer formed of a selected metallic compound (Unterrainer, col.2 lines 35-37). It would have been obvious to one of ordinary skill in the art at the time of the invention to combine the single layer of gold with the waveguide taught above to function as a surface-plasmon carrying layer (Unterrainer, col.2 lines 37-38), and additionally, it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use as a matter of obvious design choice. *In re Leshin*, 227 F.2d 197, 125 USPQ 416 (CCPA 1960).

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With respect to claim 9, Xu and Unterrainer teach the cascade laser as outlined in the rejection to claim 1, and further teach a plurality of quantum well structures collectively generating at least an upper lasing state, lower lasing state, and a relaxation state (Xu, fig.1a) such that said upper and lower lasing states are separated by an energy corresponding to an optical frequency in a range of about 1 to 10 THz (Xu, fig.3), and wherein electrons populating said lower lasing state exhibit a non-radiative relaxation via resonant emission of LO-phonons into said relaxation state (Xu, col.2-3 lines 10-4).

With respect to claims 11 and 12, Xu and Unterrainer teach the cascade laser as outlined in the rejection to claim 10, and further teach the contact layers to be heavily doped GaAs (Xu, col.1 lines 25-28).

With respect to claim 13, Xu and Unterrainer teach the cascade laser as outlined in the rejection to claim 9, and further teach the semiconductor heterostructure to be formed of Al(0.3)Ga(0.7)As/GaAs, but do not teach the active region to be composed of Al(0.15)Ga(0.85)As/GaAs. These materials are known in the art to be used with lasers. It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the laser of these known materials, since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use as a matter of obvious design choice. *In re Leshin*, 227 F.2d 197, 125 USPQ 416 (CCPA 1960).

With respect to claim 14, Xu and Unterrainer teach the cascade laser as outlined in the rejection to claim 9, and further teach the use of vertical transitions between the

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upper and lower lasing states to have less susceptibility to interface roughness and impurity scattering (Xu, col.6 lines 12-18).

With respect to claim 18, Xu and Unterrainer teach the cascade laser as outlined in the rejection to claim 1, wherein the laser would inherently function as an amplifier to incoming radiation in the 1 to 10 THz range, and additionally an input port and output port would be located at either facet of the device.

Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Unterrainer in view of Xu and further in view of Kneissl et al. (US 2004/0105471).

With respect to claim 7, Unterrainer and Xu teach the cascade laser as outlined in the rejection to claim 5, but do not specify the Au to cover the Ti. Kneissl teaches a laser structure wherein the electrical contact is formed using Ti covered with Au ([0069]). It would have been obvious to one of ordinary skill in the art at the time of the invention to combine the cascade laser of Unterrainer and Xu with the Au/Ti ordering of Kneissl to improve adhesion to the semiconductor surface as well as a good bonding surface for wire bonding (Kneissl, [0069]).

Claim 16 is rejected under 35 U.S.C. 103(a) as being unpatentable over Unterrainer.

With respect to claim 16, Unterrainer teaches the cascade laser as outlined in the rejection to claim 15, but does not specify the metal deposition technique to be involve an e-beam system. It would have been obvious to one of ordinary skill in the art at the

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time of the invention to deposit the metal layers using e-beam systems as is well known and widely used in semiconductor laser processing schemes.

A reference that is relevant, but not relied upon, speaking of forming metal layers via e-beam techniques is Weber et al. (US 5465171) col.4 lines 15-20. Weber points out that e-beam techniques such as heating, evaporation, and sputtering are well known deposition techniques.

### **Double Patenting**

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970);and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Claims 1, 8-14, and 18 are provisionally rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1, 8, 14, 17, 19-20, and 24 of copending Application No. 10661831. Although the conflicting claims are not identical, they are not patentably distinct from each other because:

Claim 1 is taught by the combination of claims 1 and 20 from '831.

Claims 8-9 are taught by claim 1 of '831.

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Claim 10 is taught by claim 19 of '831.

Claims 11-12 are taught by claim 17 of '831.

Claim 13 is taught by claim 14 of '831.

Claim 14 is taught by claim 8 of '831.

Claim 18 is taught by claims 20 and 24 of '831.

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tod T. Van Roy whose telephone number is (571)272-8447. The examiner can normally be reached on M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Minsun Harvey can be reached on (571)272-1835. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

**TVR** 

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